

<p>Form PTO-1449  <b>OIPC</b>  <b>INFORMATION DISCLOSURE CITATION</b>  <b>IN AN APPLICATION</b>  <small>MAR 29 2006      (Use several sheets if necessary)</small> </p>				Document Number (Optional)	Atticution Number	
				TSMC-03-305	10/764,913	
				Applicant	Bar-Wen Chan et al.	
				Filing Date	01/26/04	
U. S. PATENT DOCUMENTS						
EXAMINER INITIAL	DOCUMENT NUMBER	DATE	ISSUE	CLASS	SUBCLASS	SEARCH DATE & APPROXIMATE
ICL/	6500755	12/31/02	Dakshina-Murthy et al. 438	637		12/6/00
	6482726	11/19/02	Aminpur et al. 438	585		10/17/00
	6548423	4/15/03	Plat et al. 438	780		1/16/02
ICL/	6492068	12/10/02	Suzuki 430	5		1/7/00
	6541360	4/11/03	Plat et al. 438	585		4/30/01
FOREIGN PATENT DOCUMENTS						
	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION YES      NO
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)						
ICL/	U.S. Patent Application Publication US 2002/0164543 A1 Lin et al., Publication Date, 11/7/02, "Bi-layer Photolithographic Process", US. Class 430/313, filed 7/2/01.					
EXAMINER	DATE CONSIDERED					
	(Calvin Lee) (11/13/2007)					

**EXAMINER:** Initial if citation considered, whether or not citation is in conformance with MPEP § 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to the examiner.